Lam Wins Summary Judgment of Noninfringement in Tegal Suit

FREMONT, Calif., January 17, 2003-Lam Research Corporation (Nasdaq: LRCX) today announced that the United States District Court for the Northern District of California has granted Lam's motion for summary judgment of noninfringement in the patent infringement suit brought by Tegal Corporation. Tegal's claim involved the plasma reactor of Lam's Exelan® dielectric etch systems. The Court's order found that Lam did not infringe Tegal's patents either literally or by the doctrine of equivalents. Favorable resolution of the infringement question leaves pending only Lam's counterclaim against Tegal for exceptional case attorneys' fees.

This press release contains certain forward-looking statements which are subject to the Safe Harbor provisions of the Private Securities Litigation Reform Act of 1995. Such forward-looking statements relate to Lam's future plans in the litigation. Such statements are based on current expectations and are subject to risks, uncertainties and changes in condition, significance, value and effect as well as other risks detailed in documents filed with the Securities and Exchange Commission, including specifically the reports on Form 10-K for the year ended June 30, 2002, and the Form 10-Q for the quarter ended September 29, 2002, which could cause actual results to vary from expectations. The company undertakes no obligation to update the information or statements made in this press release.

Lam Research Corporation is a leading supplier of wafer fabrication equipment and services to the world's semiconductor industry. Lam's common stock trades on the Nasdaq National Market under the symbol LRCX. The Company's World Wide Web address is http://www.lamrc.com.

---

https://newsroom.lamresearch.com/2003-01-16-Lam-Wins-Summary-Judgment-of-Noninfringement-in-Tegal-Suit